

Extreme Ultraviolet Lithography (EUVL) Market 2025- CANNON, Intel, Nikon, Nuflare, Samsung, Ultratec

The study covers significant data which makes the research document a handy resource for managers, analysts, industry experts and other key people get ready-to-access and self-analyzed study along with graphs and tables to help understand market.

Pune, Feb 17, 2019 (IssueWire.com) - Global [Extreme Ultraviolet Lithography \(EUVL\) Systems Industry](#) valued approximately USD 670 million in 2016 is anticipated to grow with a healthy growth rate of more than 9.50 % over the forecast period 2017-2025. Extreme ultraviolet lithography (EUVL) is a latest process for fabricating microprocessors, this is more efficient than the present ones accessible in the Industry. Extreme ultraviolet lithography (EUVL) permit storage of extra information. This replaces other visual lithography techniques, recently used to fabricate microcircuit, that use in our devices. Few factors which helps in the growth of the Industry include ability of EUVL system provides resolving power and more productivity. However, EUVL is complex technology which needs all modern step-and-scan system to manufacture semiconductors, restricts the Industry growth.

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The objective of the study is to define Industry sizes of different segments & countries in recent years and to forecast the values to the coming eight years. The report is designed to incorporate both qualitative and quantitative aspects of the industry within each of the regions and countries involved in the study. Furthermore, the report also caters the detailed information about the crucial aspects such as driving factors & challenges which will define the future growth of the Industry. Additionally, the report shall also incorporate available opportunities in micro markets for stakeholders to invest along with the detailed analysis of competitive landscape and product offerings of key players.

Major market players in Extreme Ultraviolet Lithography (EUVL) Systems Industry are ASML, CANNON INC., Intel Corporation, Nikon Corporation, Nuflare Technology Inc., Samsung Corporation, Suss Microtec AG, Ultratech Inc., Vistec Semiconductor Systems.

Extreme Ultraviolet Lithography (EUVL) Systems Segmentation:

By Light Source:

- Laser Produced Plasmas (LLP)
- Vacuum sparks
- Gas Discharge

By Equipment:

- Light Source
- Mirrors
- Mask
- Others

By Component:

- Memory
- IDM
- Foundry

- Others

By Region:

North America

- USA
- Canada

Europe

- Germany
- U.K.
- France
- Italy
- Rest of Europe

APAC

- China
- India
- Japan
- Rest of Asia-Pacific

RoW

- Latin America
- Middle East & Africa

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